

Spin-valley coupling anisotropy and noise in CMOS quantum dots

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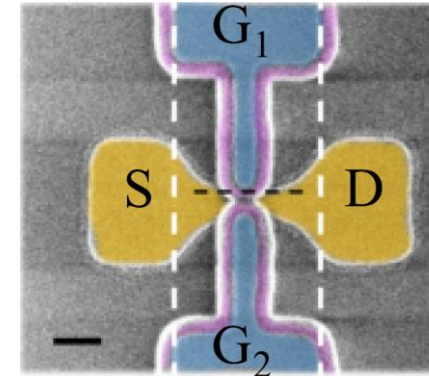
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- Spin characterization in CMOS nanowire devices
- Determination of valley splitting via T_1 measurement
- Anisotropy of spin-valley mixing
- Investigation of charge noise (on valley-splitting)

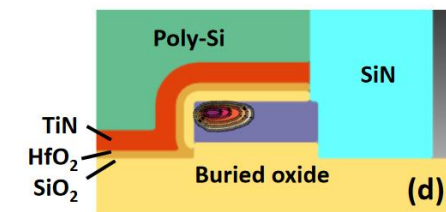
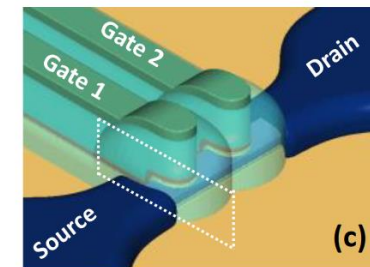


- Electrons in CMOS nanowire (width 90 nm, thickness 15 nm), fabricated on 300mm foundry-compatible wafer
- Pair of split front gates (50 nm length, separated by 50 nm)
- Electron reservoirs formed by...
 - Device 1: Ion implantation
 - Device 2: In situ growth of degenerate n-doped Si
- 6 nm SiO₂, 5 nm TiN between channel and gates



- Metallic top gate (white dashed line) 400 nm above channel, biased to +2V
- Polarized silicon bulk below buried oxide used as back gate at +5V

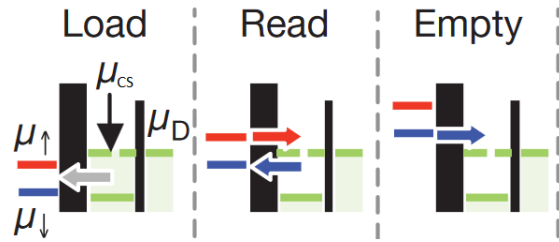
Sketch of similar type of device:



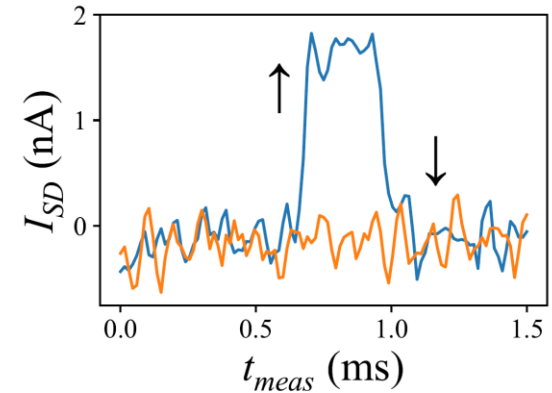
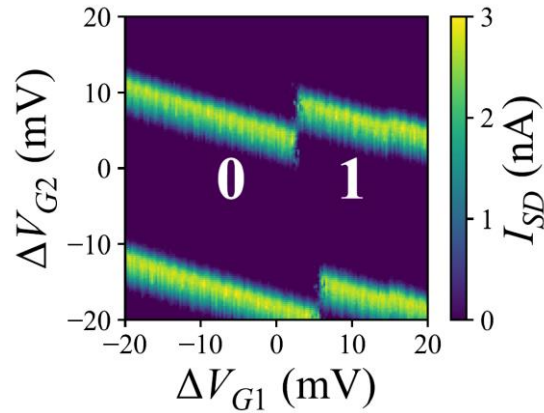
From [1]

Readout of spin state

- Energy-selective readout scheme



From [2]

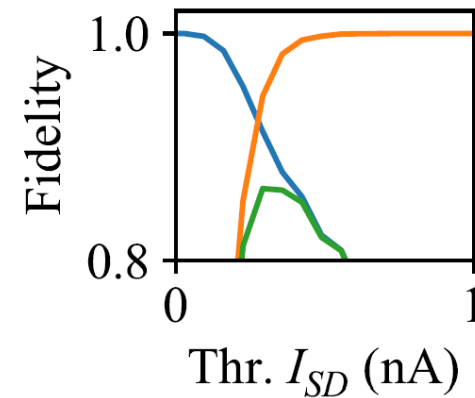
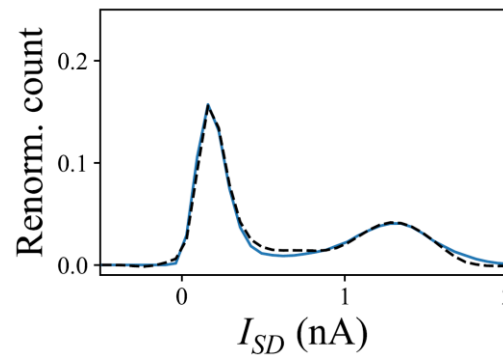


- Binned histogram of maximum I_{SD}
To determine ideal threshold current I_{thr} , calculation as in Ref. [2]:

$$F_{\downarrow} = 1 - \int_{I_T}^{\infty} N_{\downarrow}(I) dI$$

$$F_{\uparrow} = 1 - \int_{-\infty}^{I_T} N_{\uparrow}(I) dI$$

$$V = F_{\downarrow} + F_{\uparrow} - 1$$



Avg. readout fidelity above 92%,
and 86% visibility

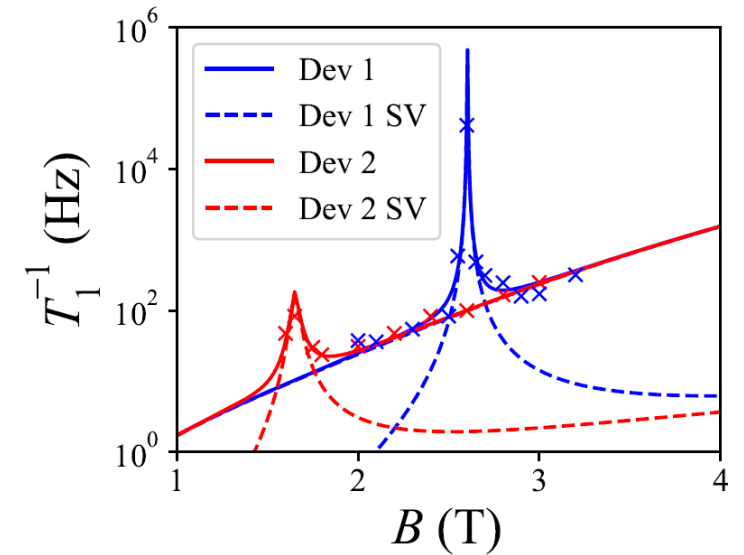
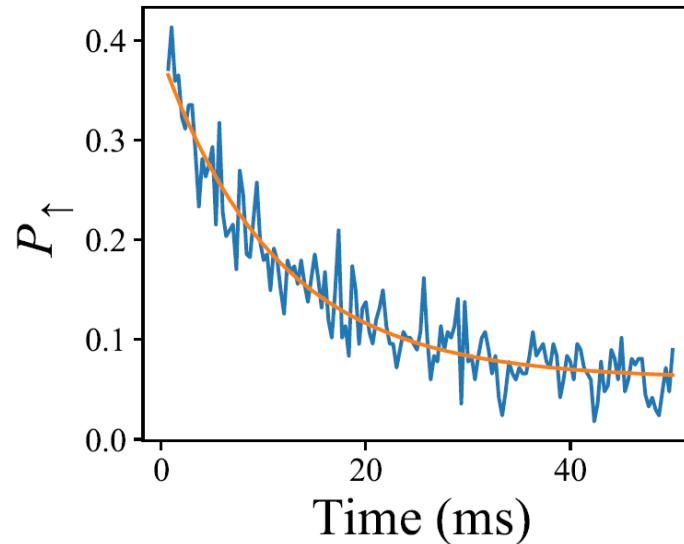
T_1 measurements & valley splitting

- Load electron with random spin orientation, then probe spin up population after given waiting time
- Hotspot in relaxation rate where E_{VS} matches E_Z
- Fit to model from Ref. [3]:

$$T_1^{-1} = \Gamma_{Ph,SV} + \Gamma_{JN,SO} + \Gamma_{Ph,SO}$$

- $\Gamma_{Ph,SV}$: Relaxation rate due to spin-valley mixing & coupling to phonons
- $\Gamma_{JN,SO}$: Relaxation rate due to SO-coupling via Johnson-Nyquist (thermal) noise
- $\Gamma_{Ph,SO}$: Relaxation rate due to SO-coupling via phonons

- Phonon-mediated mechanism dominates at high fields ($\Gamma_{JN,SV}$ neglected)

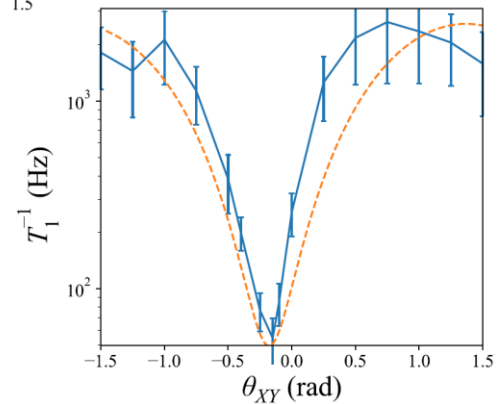
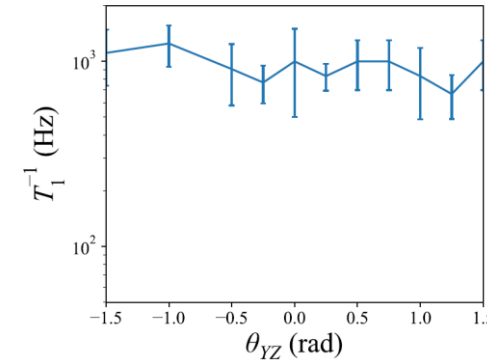
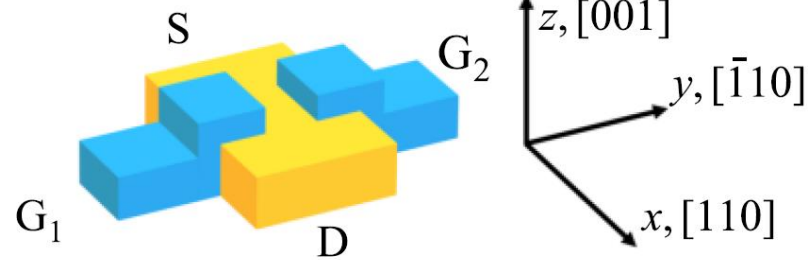


- $E_{VS} = 300 \pm 13 \mu\text{eV}$
- $E_{VS} = 191 \pm 16 \mu\text{eV}$
- SV-anticrossing gap of $0.2 \pm 3 \mu\text{eV}$ ($4.0 \pm 3 \mu\text{eV}$) (?)

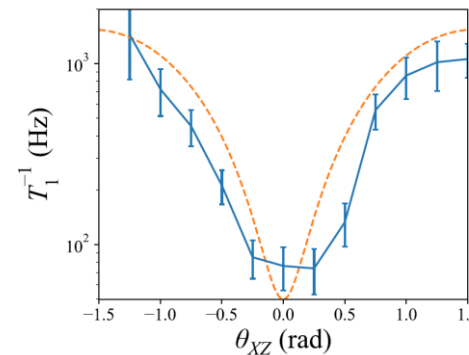
Similar rates outside hotspots indicate similar overall structure of quantum dots in the 2 devices

Anisotropy of spin-valley mixing

- SV-mixing expected to vanish in presence of >1 mirror planes
- Presence of hotspot indicates lower symmetry
- It is expected that spin-valley mixing vanishes for $\mathbf{B} \parallel \mathbf{x}$, and remaining projection leads to $|\langle v_1 \uparrow | H_{\text{SOC}} | v_2 \downarrow \rangle|^2 \propto \sin^2 \theta$
- XY-plane:** NW axis not perfectly aligned with coil axes
- XZ-plane:** different due to 2nd order anisotropy of gate overlap

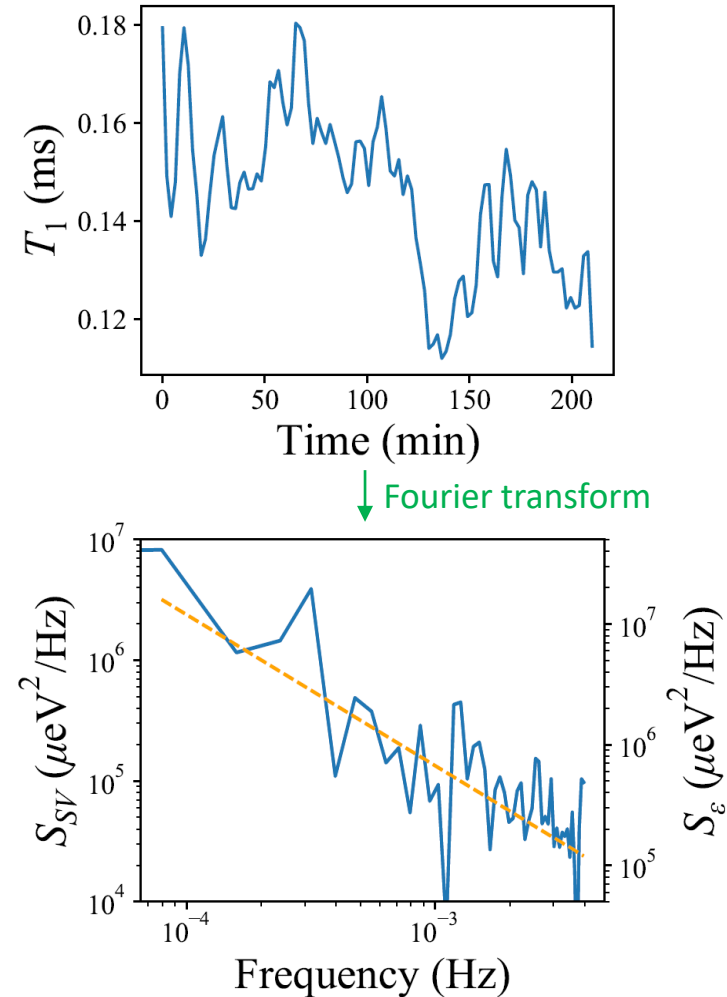


(at B-field close to hotspot)



Effect of charge noise on spin-valley mixing

- Valley splitting arises from strong confinement against top interface -> sensitive to electric fields; assume linear dependence for small noise amplitude
- Sit next to hotspot and record time evolution of T_1
- PSD follows $1/f$ dependence: $23\mu\text{eV}^2/\text{Hz}$ extrapolated at 1 Hz, corresponding to fluctuation of spin precession $\sim 0.6 \text{ GHz}/\sqrt{\text{Hz}}$
 - faster than hyperfine decoherence rate in nat. Si
 - On the order of dec. rate in charge and valley qubits



- Fast & reproducible spin characterization in CMOS nanowire devices
- Similar SOI-induced relaxation rates in both devices (outside of hotspots)
- Anisotropy measurement of spin-valley coupling via relaxation, strong symmetry plane \perp NW axis
- Strong low-frequency fluctuations could be detrimental for operation as spin-valley or valley qubit

